

ABSTRACT AMENDMENTS

Rewrite the Abstract of the Disclosure to read --

ABSTRACT OF THE DISCLOSURE

Method of thin film deposition especially in reactive conditions. Optical coatings with negligible optical absorption, of high quality and low cost even on unheated substrates are deposited using an RF/pulsed DC plasma RF/pulsed DC bias generates a plasma in front of the substrate. This plasma allows obtaining the right stoichiometry of the deposited film by increasing the reactivity of the reactive gas present in the plasma and, in addition, introduces an energetic ion bombardment of the substrate before and during the growth of the film which improves the adherence and the deposit compactness.